

PATENT APPLICATION
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

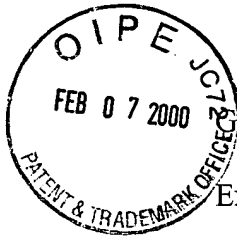
In re application of

KAWABE, YASUMASA, et al.

Appln. No.: 09/295,329

Filed: April 21, 1999

For: POSITIVE PHOTOSENSITIVE RESIN COMPOSITION



Group Art Unit: 1752

Examiner: Clarke, Y.

8/a
[Signature]

AMENDMENT UNDER 37 C.F.R. § 1.111

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

This Amendment is submitted in response to the Office Action dated October 6, 1999. A Petition for a one-month extension of time is being concurrently filed, making a response due on or before February 7, 2000 (February 6, 2000 being a Sunday). Please amend the above-identified application as follows:

IN THE SPECIFICATION:

Page 18, line 12, delete "3-ethoxypropionate" and replace with -- 3-ethoxypropionate.

Page 71, Table 8, last row, delete "Ex. 7" and replace with -- Ex. 7b --.

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IN THE CLAIMS:

2 (amended). A positive photosensitive resin composition comprising:

- (A) a polymer which has bridged alicyclic hydrocarbon skeletons and decomposes by the action of an acid to thereby become alkali-soluble,
- (B) a compound which generates an acid upon irradiation with actinic rays,

AI
[Signature]
DZ